

Title (en)  
OPTICAL ARRANGEMENT AND LITHOGRAPHY APPARATUS

Title (de)  
OPTISCHE ANORDNUNG UND LITHOGRAPHIEANLAGE

Title (fr)  
AGENCEMENT OPTIQUE ET INSTALLATION DE LITHOGRAPHIE

Publication  
**EP 3948423 A1 20220209 (DE)**

Application  
**EP 20714577 A 20200325**

Priority  
• DE 102019204165 A 20190326  
• EP 2020058366 W 20200325

Abstract (en)  
[origin: WO2020193633A1] An optical arrangement (200) for a lithography apparatus (100A, 100B), comprising a microsystem (202) having a mirror array (204), wherein a respective mirror (206) of the mirror array (204) is configured to reflect working light (108A, 108B) of the lithography apparatus (100A, 100B) at its front side (208) and a measurement beam (L, 224) at its rear side (220), one or more radiation sources (226, 310) provided outside the microsystem (202) and configured to provide the respective measurement beam (L, 224), and one or more sensor units (230, 804, 1200) configured to detect a tilt angle (a) of a respective mirror (206) depending on the respectively reflected measurement beam (L', 224').

IPC 8 full level  
**G03F 7/20** (2006.01); **G02B 26/08** (2006.01)

CPC (source: EP US)  
**G02B 5/0816** (2013.01 - US); **G02B 26/0833** (2013.01 - EP); **G03F 7/70075** (2013.01 - EP US); **G03F 7/70116** (2013.01 - EP US); **G03F 7/7085** (2013.01 - EP US); **G01S 17/32** (2013.01 - US)

Citation (search report)  
See references of WO 2020193633A1

Designated contracting state (EPC)  
AL AT BE BG CH CY CZ DE DK EE ES FI FR GB GR HR HU IE IS IT LI LT LU LV MC MK MT NL NO PL PT RO RS SE SI SK SM TR

Designated extension state (EPC)  
BA ME

DOCDB simple family (publication)  
**WO 2020193633 A1 20201001**; CN 113632010 A 20211109; DE 102019204165 A1 20201015; EP 3948423 A1 20220209; US 11402760 B2 20220802; US 2022004107 A1 20220106

DOCDB simple family (application)  
**EP 2020058366 W 20200325**; CN 202080023594 A 20200325; DE 102019204165 A 20190326; EP 20714577 A 20200325; US 202117480800 A 20210921